

**FABRICATION AND CHARACTERIZATION OF
TiO₂/Cu/TiO₂ MULTILAYER THIN FILMS FOR
THERMOLUMINESCENCE DOSIMETRY USING
RF/DC SPUTTERING**

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THERMOLUMINESCENCE DOSIMETRY USING
RF/DC SPUTTERING**

by

IDRISS ALI SALEH ALKADEM

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TABLE OF CONTENTS

ACKNOWLEDGEMENT.....	ii
TABLE OF CONTENTS	iii
LIST OF TABLES	ix
LIST OF FIGURES	xi
LIST OF SYMBOLS	xvi
LIST OF ABBREVIATIONS	xvii
LIST OF APPENDICES	xviii
ABSTRAK	xix
ABSTRACT	xxi
CHAPTER 1 INTRODUCTION	1
1.1 Background of the study	1
1.2 Problem statement.....	3
1.3 The motivation behind the research.....	4
1.4 Research objectives.....	5
1.5 Significance of the study.....	6
1.6 Scope of the study	6
1.7 Thesis outline	7
CHAPTER 2 LITERATURE REVIEW	9
2.1 Introduction.....	9
2.2 Luminescence phenomena	9
2.2.1 The luminescence centers in the (TL) light emission	10
2.2.2 TL: Historical perspective and research Use	11
2.2.3 TL dosimetry materials	12
2.2.4 Mechanism of TL.....	13
2.2.4(a) Before irradiation.....	14

	2.2.4(b) Irradiation.....	14
	2.2.4(c) Heating.....	15
2.3	Radiation sources in TL dosimetry studies	18
2.3.1	Interaction of radiation with matter in TL dosimetry	19
2.3.2	Photoelectric effect	20
2.3.3	Compton scattering	21
2.3.4	Pair production.....	22
2.3.5	Relevance to TL materials and thin films	23
2.4	Applications of thermoluminescent dosimeters (TLDs).....	23
2.4.1	Diagnostic radiology	23
2.4.2	Radiotherapy	24
2.4.3	Radiation protection and personnel dosimetry	24
2.4.4	Environmental monitoring	24
2.4.5	Brachytherapy	25
2.5	Dosimeter properties	25
2.5.1	Glow curve	25
2.5.2	Thermal treatments and trap stability.....	26
2.5.3	Sensitivity..	27
2.5.4	Linearity and dose-response.....	28
2.5.5	Energy response	28
2.5.6	Fading.....	29
2.5.7	Reproducibility and stability.....	30
2.5.8	Minimum detectable dose (MDD)	30
2.6	Crystal structure and properties of TiO_2	30
2.6.1	Fundamental defects in TiO_2	32
2.6.1.1	Intrinsic defects	32
2.6.1.2	Extrinsic defects.....	33

2.7	TiO ₂ thin-film growth	34
2.7.1	Multilayer TiO ₂ /Cu/TiO ₂ structures	34
2.7.2	Defect-related luminescence in TiO ₂ thin films	35
2.8	Synergy of TiO ₂ with Cu as a thin film	36
2.8.1	Morphology and crystal structure	36
2.8.2	Optical and electronic properties	37
2.8.3	Implications for multilayer TLDs	37
2.8.4	TiO ₂ -based TL dosimeters	38
2.8.5	Use of TiO ₂ as an activator for TL dosimetry	41
2.8.6	Thin films as TL dosimeters	42
CHAPTER 3 METHODOLOGY		50
3.1	Introduction	50
3.2	Fabrication of TiO ₂ /Cu/TiO ₂ multilayer thin films via RF and DC sputtering	52
3.2.1	Cleaning procedure for glass substrate	52
3.2.2	Sputtering deposition setup	53
3.3	Deposition of TiO ₂ /Cu/TiO ₂ multilayer thin films	56
3.3.1	Thin film deposition parameters	56
3.3.2	Thickness parameters for multilayer films	57
3.4	Characterization of multilayer TiO ₂ /Cu/TiO ₂ thin films	61
3.4.1	X-ray diffraction (XRD)	61
3.4.2	Ultraviolet-visible (UV-vis) spectroscopy	63
3.4.3	Sample cleaner ZONESEMI equipment	65
3.4.4	Field emission scanning electron microscopy (FESEM)	66
3.4.5	Atomic force microscopy (AFM)	68
3.4.6	Photoluminescence (PL) spectrometer system	69
3.4.7	Irradiation of TiO ₂ /Cu/TiO ₂ thin film	71
3.4.8	Exposure to X-ray	72

3.4.9	Exposure to a γ -ray source	74
3.4.10	TLD-100 calibration	76
3.4.11	Readout process of TLD-by-TLD reader	77
3.5	Measurements of thermoluminescence properties	79
3.5.1	Optimisation of annealing temperature	79
3.5.2	Heating rate	81
3.5.3	The thermal and optical fading	82
3.6	Measurements of dosimetric properties	83
3.6.1	Dose-response and sensitivity	84
3.6.2	Minimum detectable dose (MDD)	86
3.6.3	Photon energy response S(E) or energy dependence (ED)	86
3.6.4	The effective atomic number (Z_{eff})	89
3.6.5	Calculation of kinetic energy trap parameters for the glow curve.....	90
3.6.5(a)	Order of kinetics	91
3.6.5(b)	Activation energy (trap depth)	92
3.6.5(c)	Frequency factor	93
CHAPTER 4 RESULTS AND DISCUSSION		95
4.1	Introduction	95
4.2	Characterisation of $\text{TiO}_2/\text{Cu}(x)/\text{TiO}_2$ films	95
4.2.1	XRD analysis	96
4.2.2	Optical properties	98
4.2.2(a)	The absorbance	99
4.2.2(b)	The energy band gap calculations	101
4.2.3	FE-SEM micrographs	104
4.2.4	Atomic force microscopy (AFM)	110
4.2.5	The Photoluminescence (PL) properties	111
4.2.6	Correlation between film properties and TL behavior	113

4.3	TL measurements study of TiO ₂ /Cu/TiO ₂ multilayer films.....	114
4.3.1	Optimization samples of TL response	115
4.3.1(a)	First batch: the different thicknesses of a single layer of [TiO ₂ (x nm)]......	115
4.3.1(b)	Second batch: [TiO ₂ (150nm)/Cu (25 nm)/TiO ₂ (x) _{top-layer}]......	118
4.3.1(c)	Third batch: [TiO ₂ (150 nm)/Cu (x nm) _{mid-layer} /TiO ₂ (50 nm)]......	120
4.3.2	Homogeneity response of TiO ₂ /Cu/TiO ₂ multilayer thin films	123
4.3.3	TL study and energy band gap in multilayer films.....	125
4.3.4	Comparison of TL glow curves for single and multilayer TiO ₂ films.....	127
4.3.5	Optimum annealing temperature of TiO ₂ /5 nmCu/TiO ₂ films.....	129
4.3.6	Heating rate	131
4.3.7	Thermal fading.....	134
4.3.8	Optical fading.....	138
4.4	Dosimetric properties of TiO ₂ /Cu/TiO ₂ multilayer films	140
4.4.1	Dose-response and linearity	141
4.4.2	The sensitivity (SD)	149
4.4.3	Precision... ..	151
4.4.4	Reproducibility	153
4.4.5	Minimum detectable dose (MDD)	154
4.4.6	Calculating the energy response theoretically	155
4.4.7	Analysis of kinetic parameters	160
4.4.8	Calculation of the effective atomic number (Z _{eff}).....	163
4.5	Comparison between TiO ₂ /Cu/TiO ₂ film and TLD-100 reference.	164
CHAPTER 5 CONCLUSION.....		168
5.1	Conclusion	168
5.2	Limitations	169

5.3	Recommendations and future works.....	170
	REFERENCES.....	172
	APPENDICES	
	LIST OF PUBLICATIONS	

LIST OF TABLES

	Page
Table 2.1 The phenomenon of luminescence and the methods of stimulation	10
Table 2.2 List of general characteristics of commercial TL materials dosimeters	13
Table 2.3 Annealing process for various commercial TL materials	26
Table 2.4 Structural properties of the crystalline structures of TiO ₂	31
Table 2.5 Summary of TL properties of TiO ₂ -based materials prepared by different methods.	47
Table 2.6 Summary of TL properties of various thin film dosimetric materials prepared by different techniques.	48
Table 3.1 Deposition parameters of 150 nm TiO ₂ /5 nm Cu/50 nm TiO ₂ multilayer thin film as a new dosimeter.	57
Table 3.2 The first batch shows different samples of TiO ₂ single-layer (pure) thin films prepared at different thicknesses	59
Table 3.3 The preparation of TiO ₂ /Cu/TiO ₂ multi-layer thin films for the second batch.	60
Table 3.4 The preparation of TiO ₂ /Cu(x)/TiO ₂ multi-layer thin films for the third batch.	60
Table 3.5 The TLD reader's time temperature profile (TTP) is used to read out the TiO ₂ /Cu/TiO ₂ multilayer thin film	79
Table 3.6 Fractional weights of composition using EDX tests for new dosimeters	88
Table 4.1 The percentage of crystallinity index and particle size for TiO ₂ with 25 nm Cu and 40 nm Cu	98
Table 4.2 Comparison of TiO ₂ /Cu/TiO ₂ thin film before and after annealing.	106
Table 4.3 TiO ₂ /Cu/TiO ₂ multilayer film thickness (Nominal vs. Measured)	108
Table 4.4 The highlight of the characterisation of the TiO ₂ /5 nm Cu/TiO ₂ multilayer film.	114

Table 4.5	The percentage of residual signals that fade at room temperature for the TiO ₂ /5 nm Cu/TiO ₂ multilayer film	136
Table 4.6	The percentage of optical fading residual signals in fluorescent light and sunlight for a TiO ₂ /5 nm Cu/TiO ₂ multilayer film	140
Table 4.7	X-ray TL response statistics of TiO ₂ /Cu/TiO ₂ films	143
Table 4.8	γ-ray TL response statistics of TiO ₂ /Cu/TiO ₂ films.	143
Table 4.9	Comparison of the sensitivity and relative sensitivity of TiO ₂ (150 nm)/Cu (5 nm)/TiO ₂ (50 nm) multilayer thin film to TLD-100 chips.....	150
Table 4.10	The relative total standard deviation S.r (experimental and theoretical) of a TiO ₂ (150 nm)/Cu (5 nm)/TiO ₂ (50 nm) multilayer film as a function of dosage	151
Table 4.11	The MMD of TiO ₂ (150 nm) /Cu(5 nm) /TiO ₂ (50 nm) multilayer thin film using different methods	154
Table 4.12	The mass-energy absorption coefficient (μ_{en}/ρ) of each element in TiO ₂ (150 nm)/Cu (5 nm)/TiO ₂ (50 nm) for different photon energy responses	157
Table 4.13	The energy dependency S(E) and relative energy response (RER) of the TiO ₂ /5nm Cu/TiO ₂ multilayer film	160
Table 4.14	Kinetic parameters obtained for TiO ₂ /Cu 5 nm/ TiO ₂ multilayer film using the peak shape method.....	161
Table 4.15	Activation energy (eV), frequency factor (s), and lifetime (t _{1/2}) of the multilayer film assessed by the peak shape method	162
Table 4.16	Calculations of Z _{eff} for TiO ₂ /Cu/TiO ₂	164
Table 4.17	Comparison of the new dosimeter with TLD-100; TLD-100 reference values are approximate from published data	164

LIST OF FIGURES

	Page
Figure 2.1	The thermoluminescence phenomenon process, where transitions a, b, c, and d represent the different electron transitions..... 14
Figure 2.2	The bottom curve shows the trend of the photon energy E as a function of the target substance's atomic number Z, below which photoelectric absorption (photoabsorption) is the main response mechanism, while the upper curve shows the energy above which pair production is dominant. The shaded area between the two curves represents the Compton scattering-dominated field 20
Figure 2.3	Schematic diagram for photoelectric interaction..... 21
Figure 2.4	The schematic diagram for Compton interaction 22
Figure 2.5	Pair the production interaction schematic exhibiting annihilation radiation..... 22
Figure 2.6	The TLD glow curve and time-temperature profile (TTP)..... 26
Figure 2.7	Depiction of the different regions that could be observed in a plot of TL as a function of dosage 28
Figure 2.8	The photon energy responses for selected TLD materials, with soft tissue as the reference material ($Z_{\text{eff}} = 7.35$) 29
Figure 2.9	The crystal structures of the TiO_2 polymorphs (a) anatase (tetragonal), (b) rutile (tetragonal), and (c) brookite (orthorhombic)..... 32
Figure 3.1	The flowchart of the research methodology. 51
Figure 3.2	a) The microscope glass cover as substrate; b) a beaker containing acetone and the substrate inside; c) Branson 1510 ultrasonic cleaner; d) nitrogen gas. 53
Figure 3.3	a) The RF and DC sputtering machine and b) schematic diagram 53
Figure 3.4	The target materials to produce $\text{TiO}_2/\text{Cu}/\text{TiO}_2$ multilayer thin films by RF&DC sputtering: a) TiO_2 target, b) Cu target..... 54
Figure 3.5	Tools utilized to fabricate $\text{TiO}_2/\text{Cu}/\text{TiO}_2$ multilayer thin films: a) glass substrate after cleaning, b) thermal tape, and c) the stainless-steel platform 54

Figure 3.6	a) Depictions of $\text{TiO}_2/\text{CuTiO}_2$ samples where the target materials (TiO_2 and Cu) and glass substrates were both positioned in the vacuum chamber before determination of the preparation parameters, b) Samples after coating on a glass substrate 55
Figure 3.7	TiO_2 multilayer films with a fixed Cu mid-layer and varied TiO_2 top layers for samples in an aluminum holder 59
Figure 3.8	The films of $\text{TiO}_2/\text{Cu}(x)/\text{TiO}_2$ multilayers and TiO_2 single layers are deposited on a glass substrate. 60
Figure 3.9	(a) X-ray diffraction (XRD) equipment and (b) schematic diagram of X-ray diffraction..... 63
Figure 3.10	(a) The UV-Vis light spectrophotometer-1800 and (b) an illustration of the working principle of the equipment..... 65
Figure 3.11	ZONESEMI equipment to clean the samples. 66
Figure 3.12	a) A photo of a field emission scanning electron microscope (FE-SEM), equipped with EDX, and b) a schematic showing the working principle of the FESEM equipment..... 67
Figure 3.13	(a) The atomic force microscopy (AFM) machine and (b) an illustration of the working principle of AFM. 69
Figure 3.14	a) A photograph of the photoluminescence (PL) and b) a schematic diagram of the working principle of the PL spectrometer..... 70
Figure 3.15	a) Glass cutter, b) the electronic balance to weigh the samples 71
Figure 3.16	The simple schematic presents the experimental setup and components for the process of irradiating samples with X-rays: a) Toshiba KXO-50S X-ray; b) Perspex phantom with holes for the ion chamber, TLD-100, and new samples; c) the ion chamber; and d) the electrometer connected to the ion chamber..... 74
Figure 3.17	The schematic diagram for exposing samples to radiation using a gamma source in the air: a) ^{241}Am source; b) perspex phantom; c) ion chamber; d) TLD-100; and e) the new samples of $\text{TiO}_2/\text{Cu}/\text{TiO}_2$ 75
Figure 3.18	a) TLD reader Harshaw 3500 attached to a PC containing software with N_2 gas, and b) a diagram..... 78
Figure 3.19	TLD furnace for the annealing process. 81
Figure 3.20	Peak shape method for calculating form parameters..... 91

Figure 4.1	XRD diffraction spectra of (a) single-layer TiO_2 and $\text{TiO}_2/\text{Cu}(x)/\text{TiO}_2$ multilayer thin films with various $\text{Cu}(x)$ interlayer thicknesses: b) 5 nm, c) 10 nm, d) 25 nm, e) 40 nm, and f) 50 nm annealed at 400 °C/1 h.....	97
Figure 4.2	The absorbance spectra of the TiO_2 single layer and $\text{TiO}_2/\text{Cu}(x)/\text{TiO}_2$, where $x = 5, 10, 25, 40$, and 50 nm, annealed at 400 °C/1 h.....	99
Figure 4.3	The energy band gap was calculated using the Tauc plot of the single layer of TiO_2 , and $\text{TiO}_2(150 \text{ nm})/\text{Cu}(x)/\text{TiO}_2(50 \text{ nm})$, where $x = 5, 10, 25, 40$, and 50, and annealing at 400 °C/h.....	102
Figure 4.4	FESEM and cross-section image of the pure single layer of TiO_2 film annealing at 400 °C/1 h.....	105
Figure 4.5	FE-SEM images of $\text{TiO}_2 (150 \text{ nm})/\text{Cu} (5 \text{ nm})/\text{TiO}_2 (50 \text{ nm})$ thin films:(a) Without annealing; (b) After annealing at 400 °C.....	106
Figure 4.6	FESEM and cross-section images of $\text{TiO}_2/\text{Cu}(x)/\text{TiO}_2$ multilayer thin films at Cu interlayer thicknesses of a) 5 nm, b) 10 nm, c) 50 nm, annealing at 400 °C/1 h.....	107
Figure 4.7	The EDX spectrum of $\text{TiO}_2(150 \text{ nm})/\text{Cu} (5 \text{ nm})/\text{TiO}_2(50 \text{ nm})$ multilayer thin films.	109
Figure 4.8	The surface AFM images of TiO_2 thin films deposited on glass substrates for (a) a single layer (200 nm) and $\text{TiO}_2/\text{Cu}/\text{TiO}_2$ multilayer thin films with varied layer thicknesses of Cu at (b) 5 nm, (c) 25 nm, and (d) 50 nm at 400 °C/1h.....	111
Figure 4.9	Photoluminescence (PL) spectra were obtained for $\text{TiO}_2/\text{Cu}/\text{TiO}_2$ multilayer thin film, where $\text{Cu}_{(x)} = 5$ and 50 nm.....	112
Figure 4.10	The glow curves of different layers of $\text{TiO}_2(x)_{\text{single-layer}}$, where $x = 20, 30, 50, 100$, and 150 nm.....	116
Figure 4.11	TL intensity as a function of different thicknesses of the single layer of TiO_2 (pure).	117
Figure 4.12	The glow curves of $[\text{TiO}_2 (150 \text{ nm})/\text{Cu} (25 \text{ nm})/\text{TiO}_2(x \text{ nm})_{\text{top-layer}}]$ multilayers for different top TiO_2 layer thicknesses.	118
Figure 4.13	The TL intensity as a function of the different thicknesses of the top layer of TiO_2	119

Figure 4.14	The glow curve spectra of $\text{TiO}_2/\text{Cu}(x)/\text{TiO}_2$ multilayers with various thicknesses of $\text{Cu}(x)$ layers, where $x = 0, 5, 10, 25, 40$, and 50 nm	120
Figure 4.15	The TL intensity as a function of the different thicknesses for the mid-layer of Cu.....	122
Figure 4.16	The homogeneity of the batch of TL response of a $[150 \text{ nm TiO}_2/5 \text{ nm Cu}/50 \text{ nm TiO}_2]$ multilayer film.	124
Figure 4.17	Energy band gap schematic diagrams of Cu and TiO_2 , (a) before and (b) after contact.....	126
Figure 4.18	Comparison of TL glow curves, a) $\text{TiO}_2(200 \text{ nm})$ of a single layer, and b) $150 \text{ nm TiO}_2/5 \text{ nm Cu}/50 \text{ nm TiO}_2$ multilayer films subjected to 500 mGy	129
Figure 4.19	TL response and standard deviation for $\text{TiO}_2/5 \text{ nm Cu}/\text{TiO}_2$ multilayer film at various annealing temperatures for 60 minutes.....	130
Figure 4.20	TL response and corresponding standard deviation for $\text{TiO}_2/5 \text{ nm Cu}/\text{TiO}_2$ multilayer film at 400°C with varying annealing times.	131
Figure 4.21	TL intensity of the optimum of $\text{TiO}_2/5 \text{ nm Cu}/\text{TiO}_2$ multilayer film as a function of heating rate.....	132
Figure 4.22	The effect of different heating rates on the glow peak temperature of $\text{TiO}_2/5 \text{ nm Cu}/\text{TiO}_2$ multilayer thin film exposed to 1 Gy X-ray dose.	133
Figure 4.23	The glow curve of a multilayer thin film composed of $\text{TiO}_2/5 \text{ nm Cu}/\text{TiO}_2$ was subjected to an X-ray dose of 1 Gy at different heating rates.	134
Figure 4.24	The storage behavior of the residual signal in the $\text{TiO}_2/5 \text{ nm Cu}/\text{TiO}_2$ multilayer film after exposure to 500 mGy of X-ray radiation	137
Figure 4.25	Thermoluminescence spectra of thermal fading glow curves in a 500 mGy X-ray-irradiated $\text{TiO}_2/5 \text{ nm Cu}/\text{TiO}_2$ multilayer film at ambient temperature during a given period.....	137
Figure 4.26	The optical fading behavior of a $\text{TiO}_2/5 \text{ nm Cu}/\text{TiO}_2$ multilayer film subjected to 1000 mGy and stored under fluorescent light	139
Figure 4.27	The optical fading behavior of a $\text{TiO}_2/5 \text{ nm Cu}/\text{TiO}_2$ multilayer film subjected to 1000 mGy and stored under sunlight	139

Figure 4.28	The linearity and TL responses of TLD-100 and the optimum sample of $\text{TiO}_2/5 \text{ nm Cu/TiO}_2$ multilayer thin film exposed to various X-ray doses ranging from 50-1500 mGy.....	142
Figure 4.29	The linearity and TL responses of TLD-100 and the optimum sample of $\text{TiO}_2/5 \text{ nm Cu/TiO}_2$ multilayer thin film exposed to various γ -ray doses ranging from 30-1500 mGy.....	142
Figure 4.30	Linear thermoluminescence spectra of $\text{TiO}_2/\text{Cu } 5 \text{ nm } / \text{TiO}_2$ with X-ray radiation doses up to 1500 mGy.....	146
Figure 4.31	Linear thermoluminescence spectra of $\text{TiO}_2/\text{Cu } 5 \text{ nm } / \text{TiO}_2$ with γ -ray radiation doses up to 1500 mGy.....	147
Figure 4.32	The linearity index $f(D)$ as a function of the different doses used for irradiating the $\text{TiO}_2/5 \text{ nm Cu/TiO}_2$ film with X-ray radiation doses ranging from 50 to 1500 mGy.....	148
Figure 4.33	The linearity index $f(D)$ as a function of the different doses used for irradiating the $\text{TiO}_2/5 \text{ nm Cu/TiO}_2$ film with γ -ray radiation doses ranging from 30 to 1500 mGy.....	148
Figure 4.34	The relative standard deviation of a $\text{TiO}_2 / \text{Cu } 5 \text{ nm} / \text{TiO}_2$ multilayer film as a function of dosage	152
Figure 4.35	The TL intensity against nine cycles of reproducibility characteristics of a $\text{TiO}_2/5 \text{ nm Cu/TiO}_2$ multilayer thin film subjected to 500 mGy of X-ray radiation	153
Figure 4.36	Calculated relative energy response or energy dependence $S(E)$ of a multilayer thin film consisting of $\text{TiO}_2/\text{Cu } 5 \text{ nm} / \text{TiO}_2$	159
Figure 4.37	Peak analysis of the glow curve in the $\text{TiO}_2/\text{Cu } (5 \text{ nm}) / \text{TiO}_2$ multilayer exposed to 800 mGy X-ray radiation dose to determine the necessary geometric parameters	161

LIST OF SYMBOLS

$^{\circ}\text{C}$	Degree Celsius
α	Absorption coefficient
a_i	Fractional contents of electrons of an element
B	Kinetics order
B^*	Mean thermoluminescence background signal
C	Coulomb
D	Absorbed dose
D_0	Minimum detectable dose
e^-	Electron
E_g	Band gap energy
E_a	Trap depth (activation energy)
$F(D)$	Linearity index
h	Hour
h^+	Hole
$h\nu$	Energy of a photon
I_m	Maximum intensity
k	Boltzmann's constant
K	Kelvin
λ	Wavelength
min	Minute

LIST OF ABBREVIATIONS

2D	Two-dimensional
AFM	Atomic force microscopy
BeO	Beryllium oxide
CaF ₂	Calcium fluoride
CF	Calibration factor
Co	Cobalt
Cu	Copper
DC	Direct current
EDX	Energy Dispersive X-ray
FE-SEM	Field Emission Scanning Electron Microscopy
Gy	Gray
IR	Ionizing radiation
LiF	Lithium fluoride
NA	Avogadro's number
PL	Photoluminescence
RF	Radio frequency
Ti	Titanium
TiO ₂	Titanium dioxide
UV-Vis	Ultraviolet-visible light
XRD	X-ray diffraction
2D	Two-dimensional
AFM	Atomic force microscopy
BeO	Beryllium oxide
CaF ₂	Calcium fluoride
CF	Calibration factor
Co	Cobalt
Cu	Copper
DC	Direct current

LIST OF APPENDICES

Appendix A	The homogeneity of the TiO ₂ /5 nm Cu/TiO ₂ multilayer film.
Appendix B	The TL response of TiO ₂ /5 nm Cu/TiO ₂ multilayer film exposed to X- and γ -ray irradiation.
Appendix C	The annealing procedure of the TiO ₂ /5 nm Cu/TiO ₂ multilayer film was exposed to 500 mGy x-ray radiation doses.
Appendix D	The heating rate of a TiO ₂ /5 nm Cu/TiO ₂ multilayer film exposed to 0.3 Gy of X-ray radiation.
Appendix E	The reproducibility of the TiO ₂ /5 nm Cu/TiO ₂ multilayer film irradiated with 500 mGy X-ray.
Appendix F	The minimum detectable dose (MDD) of TiO ₂ /5 nm Cu/TiO ₂ multilayer film exposed to 0.3 Gy X-ray radiation doses.
Appendix G	The mass energy attenuation coefficient and the corresponding energy of each element.

FABRIKASI DAN PENCIRIAN FILEM NIPIS BERBILANG LAPISAN
TiO₂/Cu/TiO₂ UNTUK DOSIMETRI TERMOPENDARCAHAYA
MENGGUNAKAN PENYEMBURAN RF/DC

ABSTRAK

Dosimetri Termopendarcahaya (TLD) merupakan peranti yang digunakan secara meluas dan diperbuat daripada bahan fosfor, seramik, dan kristal, yang dikenali kerana pengeluaran luminesens yang tinggi bagi setiap dos sinaran yang diserap. Walau bagaimanapun, ia menghadapi beberapa cabaran utama, termasuk kehilangan isyarat yang cepat, penyerakan sinaran, ketepuan pada dos tinggi, serta proses anil yang kompleks untuk penggunaan semula. Kajian ini bertujuan untuk membangunkan dosimeter filem nipis berstruktur berbilang lapisan TiO₂/Cu/TiO₂ yang baharu bagi mengatasi kekangan ini serta meningkatkan prestasi dan kebolehpercayaan dalam pengukuran sinaran. Dalam kajian ini, dosimeter berbilang lapisan telah difabrikasi menggunakan kaedah penyemburan frekuensi radio (RF) dan arus terus (DC), yang membolehkan kadar pemendapan lebih pantas serta menjamin ketulenan dan ketebalan lapisan yang seragam. Tiga kumpulan filem berbilang lapisan telah dihasilkan untuk analisis. Kumpulan pertama terdiri daripada satu lapisan tunggal TiO₂ tulen dengan ketebalan 20, 30, 50, 100, dan 150 nm. Kumpulan kedua berstruktur TiO₂ (150 nm)/Cu (25 nm)/TiO₂ (x nm), dengan nilai x sebanyak 20, 30, 50, 100, dan 150 nm. Kumpulan ketiga terdiri daripada struktur TiO₂ (150 nm)/Cu (x nm)/TiO₂ (50 nm), dengan nilai x sebanyak 5, 10, 25, 40, dan 50 nm. Ciri struktur, morfologi dan optik filem telah dianalisis menggunakan pelbagai teknik, termasuk XRD, UV-VIS, FESEM, EDX, AFM, dan PL. Filem berbilang lapisan ini menunjukkan tindak balas yang baik terhadap pendedahan sinaran-X dan gamma sehingga 1500 mGy. Pengukuran

sensitiviti menunjukkan bahawa filem ini kira-kira 2.25 kali kurang sensitif berbanding TLD-100 bagi sinaran X dan kira-kira 9.8 kali kurang sensitif bagi sinaran gamma. Keamatan termoluminasi (TL) optimum dikenal pasti dalam konfigurasi TiO_2 (445 nm)/Cu (14.2 nm)/ TiO_2 (130 nm), dengan keamatan TL tertinggi dicapai selepas rawatan anil pada suhu 400°C selama 2 jam. Dos boleh dikesan minimum (MDD) adalah 4.549 mGy, dan kadar pemanasan optimum untuk lengkung cahaya TL ialah $5^\circ\text{C}/\text{saat}$. Dapatan kajian ini menunjukkan bahawa filem berbilang lapisan $\text{TiO}_2/\text{Cu}/\text{TiO}_2$ berpotensi besar dalam aplikasi dosimetri termopendarcahaya.

**FABRICATION AND CHARACTERIZATION OF TiO₂/Cu/TiO₂
MULTILAYER THIN FILMS FOR THERMOLUMINESCENCE
DOSIMETRY USING RF/DC SPUTTERING**

ABSTRACT

Thermoluminescent dosimeters (TLDs) are widely used devices made from phosphors, ceramics, and crystals, known for their high luminescence output per absorbed dose. However, they face significant challenges, including rapid signal fading, radiation scattering, saturation at high doses, and complex annealing processes for reuse. This study aims to develop a novel TiO₂/Cu/TiO₂ multilayer thin film dosimeter that addresses these limitations, improving the performance and reliability of radiation measurement. The multilayer dosimeters were fabricated using radio-frequency (RF) and direct current (DC) sputtering methods, enabling faster deposition rates while ensuring high purity and uniformity. Three batches of multilayer films were produced for analysis. The first batch included a single layer of pure TiO₂ with thicknesses of 20, 30, 50, 100, and 150 nm. The second batch was structured as TiO₂ (150 nm)/Cu (25 nm)/TiO₂ (x nm), with x values of 20, 30, 50, 100, and 150 nm. The third batch consisted of TiO₂ (150 nm)/Cu (x nm)/TiO₂ (50 nm), with x values of 5, 10, 25, 40, and 50 nm. We analyzed the structural, morphological, and optical properties of the films using various techniques, including XRD, UV-VIS, FESEM, EDX, AFM, spectroscopy, and PL spectroscopy. The multilayer films demonstrated favorable responses to X-ray and gamma-ray exposure, tested up to 1500 mGy. The sensitivity measurements revealed that the films were approximately 2.25 times less sensitive than TLD-100 for X-rays and about 9.8 times less sensitive for gamma rays. The optimal TL intensity was identified in the TiO₂ (445 nm)/14.2 nm Cu/TiO₂ (130

nm) configuration, with the highest TL intensity achieved after an annealing treatment at 400°C for 2 hours. The minimum detectable dose (MDD) was found to be 4.549 mGy, and the optimal heating rate for the TL glow curve was determined to be 5°C/sec. The findings indicate that TiO₂/Cu/TiO₂ multilayer films are promising candidates for TL dosimetric applications.

CHAPTER 1

INTRODUCTION

1.1 Background of the study

Thermoluminescent dosimeters (TLDs) have been proven to be highly effective tools for detecting ionizing radiation doses. They offer numerous advantages, including ease of handling, simple TLD readout procedures, and the utilization of TL glow curves for quality control and dose estimation. Furthermore, TLDs enable individual calibration and exhibit very flat responses to photon energies, which makes them particularly suitable for precise measurements (McKeever and Moscovitch, 2003). In addition, TLDs can integrate dose accumulation over time and demonstrate considerable sensitivity to different forms of radiation, even at minimal sizes, rendering them more effective than many other dosimeters for measuring absorbed doses of ionizing radiation.

TLD materials possess appealing intrinsic properties such as a favorable effective atomic number (Z_{eff}), reasonable sensitivity, an energy-independent dose response, a wide linear dynamic range, rapid preparation, low manufacturing costs, and low fading rates (Kaur et al., 2020). Because of their compact dimensions, thermoluminescent detectors are especially appropriate for mapping radiation fields in medical applications of ionizing radiation, as well as for environmental monitoring and personal dosimetry (Aluker et al., 2016). Nonetheless, achieving high accuracy and precision in radiation dose measurement remains a significant challenge in many dosimetric applications.

A variety of materials have been utilized as TLD phosphors, including LiF, $\text{Li}_2\text{B}_4\text{O}_7$, MgB_4O_7 , and BeO, which are often referred to as tissue-equivalent materials

because their effective atomic numbers are close to that of human soft tissue ($Z_{\text{eff}} = 7.4$) (Jayachandran, 1971). In contrast, phosphors with atomic numbers ranging from 15 to 18, such as salts of alkaline earth metals and metal oxides including CaSO_4 , CaF_2 , Al_2O_3 , ZrO_2 , and TiO_2 , exhibit higher sensitivity, although they do not possess tissue equivalence (Azorín-Nieto, 1990).

Recent research has increasingly focused on the development of nanomaterials that maintain physical and chemical stability under both low and high doses of radiation. For instance, rod-shaped nanophosphor materials have demonstrated linear TL responses across a broad dose range (0.1 Gy to 10 kGy) with low fading. LiF: Cu, P, Mg TLDs have shown TL sensitivities approximately three times higher than bulk LiF: Mg, Ti (TLD-100) phosphors (Salah, Sahara et al., 2007). Similarly, the TL sensitivity of $\text{MgB}_4\text{O}_7\text{:Dy}$ nanophosphor was reported to be 0.025 times greater than that of bulk $\text{CaSO}_4\text{:Dy}$ (Lochab et al., 2007). $\text{Li}_2\text{B}_4\text{O}_7\text{:Cu}$ nanophosphors have demonstrated superior linear response and sensitivity compared to commercially available microcrystalline forms (Singh et al., 2011).

Current research efforts are emphasizing the synthesis of TLD materials incorporating nanostructured components, especially in the form of thin films. Such materials exhibit unique properties that differ markedly from their bulk counterparts due to their large surface area-to-volume ratios. The incorporation of nano-TLD components not only enhances the sensitivity and stability of thermoluminescent materials but also facilitates the miniaturization of electronic components and improves their performance in measuring low-energy radiation doses (Azorín, 2014).

This study focuses on evaluating the radiation dosimetric response of a three-layer $\text{TiO}_2\text{/Cu/TiO}_2$ thin film structure under controlled X-ray irradiation. The choice

of this specific multilayer configuration, instead of a single TiO_2 layer, is based on its potential to enhance charge transport, improve sensitivity, and achieve superior mechanical stability. The investigation is limited to copper as the intermediate conductive layer and does not extend to other metals or semiconductor combinations.

1.2 Problem statement

Although TLD-100 (LiF: Mg, Ti) remains one of the most widely used materials in radiation dosimetry, its long-term applicability is hindered by several drawbacks, including susceptibility to environmental moisture, the requirement for complex annealing cycles, rapid signal fading, dose saturation at high exposures, and limited thermal stability (McKeever, 1995a; Salah & Sahara, 2007; Swamy et al., 2014). Furthermore, while its effective atomic number ($Z_{\text{eff}} \approx 8.2$) provides near tissue-equivalence and makes it suitable for medical applications, the material's complex glow curve structure often complicates precise dose evaluation under varying irradiation conditions.

Alternative dosimeters such as $\text{CaF}_2\text{:Dy}$ (TLD-200) and LiF: Mg, Cu, P (TLD-100H) have been developed to improve sensitivity; however, they continue to suffer from severe signal fading and instability at elevated temperatures (Binder et al., 1969; Nair et al., 2018). These limitations highlight the need for novel dosimetric materials that combine high sensitivity with superior thermal and environmental stability.

Recent developments in thin-film technology have introduced titanium dioxide (TiO_2) as a promising candidate for thermoluminescence (TL) applications due to its excellent chemical stability, wide bandgap, high radiation resistance, and ability to form nanostructures with tunable optical properties (Maurício et al., 1999; Thabit et al., 2021, 2023). Unlike bulk TLD-100, thin-film systems offer the advantages of

miniaturization, easy integration with microelectronic devices, and tunable dosimetric response through controlled thickness and multilayer architectures.

Incorporating metallic interlayers such as copper (Cu) within TiO₂ multilayers provides an additional pathway to enhance TL performance. Copper can introduce efficient charge-trapping and recombination centers, improve carrier transport, and potentially increase sensitivity by facilitating energy transfer between layers. These properties may allow TiO₂/Cu/TiO₂ multilayer thin films to overcome the drawbacks of TLD-100 by providing higher sensitivity, improved thermal stability, and reduced signal fading under ionizing radiation. Despite this potential, systematic studies on TiO₂/Cu/TiO₂ multilayer thin films are scarce, and the influence of deposition parameters, interlayer effects, and film thickness on TL response remains largely unexplored (El Hajj et al., 2012).

To address these gaps, this study proposes the fabrication and characterization of TiO₂/Cu/TiO₂ multilayer thin films using magnetron sputtering. By comparing their thermoluminescent properties against the benchmark TLD-100 and investigating how structural design, deposition conditions, and interlayer engineering affect performance under ionizing radiation, this research seeks to advance the development of a new class of miniaturized, high-sensitivity, and thermally stable dosimeters for medical, industrial, and environmental radiation monitoring.

1.3 The motivation behind the research

Radiation dosimetry plays a vital role in healthcare, environmental safety, industrial quality assurance, and radiation protection. Its success is intrinsically tied to the properties of the dosimetric materials used. For example, in low-energy applications such as mammography, a dosimeter must exhibit suitable energy

dependence and stable signal retention. Efficient TL materials must facilitate high electron-hole pair generation, strong trapping mechanisms, and stable luminescent emission (Tang et al., 2021). Crystalline TL materials are common due to their light scattering properties, which enhance signal detection (Saidu et al., 2018). However, many suffer from opacity, thermal instability, or limited reproducibility.

This research is motivated by the need for a robust, energy-independent TL material that provides clear glow curves, wide linear response ranges, high sensitivity, and minimal fading. Titanium dioxide (TiO_2) stands out as a potential candidate due to its wide bandgap (3.2 eV), excellent optical and chemical stability, mechanical strength, and strong adhesion to glass (Dhar & Alford, 2014). However, its relatively high Z_{eff} results in pronounced energy dependence. Incorporating copper (a low-Z metal) as an interlayer may correct for this, helping to minimize backscatter effects and redundant radiation, thereby flattening the energy response (Pradhan et al., 1990)

1.4 Research objectives

This study primarily aims to develop and evaluate $\text{TiO}_2/\text{Cu}/\text{TiO}_2$ multilayer thin film thermoluminescent dosimeters with enhanced sensitivity, stability, and dosimetric performance for radiation monitoring. The specific objectives are as follows:

- i. To fabricate $\text{TiO}_2/\text{Cu}/\text{TiO}_2$ multilayer thin films using direct current (DC) and radiofrequency (RF) sputtering techniques, with top TiO_2 layer thicknesses varied systematically between 20 nm and 150 nm.
- ii. To characterize the structural, morphological, and optical properties of the fabricated thin films using XRD, FE-SEM, EDX, AFM, and UV-Vis spectroscopy.

- iii. To evaluate the thermoluminescent and dosimetric properties of the multilayer films, including glow curve profile, dose–response linearity in the range of 100–1500 mGy, reproducibility, sensitivity, minimum detectable dose (MDD), thermal fading, and kinetic trapping parameters.
- iv. To compare the performance of the fabricated dosimeters with that of the commercial TLD-100 material, particularly in terms of sensitivity, and under X-ray irradiation.

1.5 Significance of the study

This study contributes to the advancement of thin-film thermoluminescent materials by introducing a novel $\text{TiO}_2/\text{Cu}/\text{TiO}_2$ multilayer system. Its findings have potential implications for the design of low-cost, miniaturized dosimeters with enhanced sensitivity, suitable for medical imaging, radiotherapy, and environmental radiation monitoring (Kher & Bhatt, 2021; Abdelhalim et al., 2020). Moreover, the research fills a critical gap in the understanding of nanostructured TL materials and their interaction with ionizing radiation (Yukihara & McKeever, 2011; Rivera et al., 2015).

1.6 Scope of the study

This study focuses on the development and comprehensive evaluation of $\text{TiO}_2/\text{Cu}/\text{TiO}_2$ multilayer thin films deposited on glass substrates, fabricated via magnetron sputtering techniques. The research involves the optimization of key deposition parameters, including the thicknesses of the individual layers and the applied plasma power, to enhance thermoluminescent performance. Structural and morphological characterization of the films is conducted using X-ray diffraction

(XRD) and field emission scanning electron microscopy (FE-SEM), while elemental composition is analyzed through energy dispersive X-ray spectroscopy (EDX). Optical properties, including absorption and transmittance, are examined using ultraviolet-visible (UV–Vis) spectroscopy, and photoluminescence (PL) spectroscopy is utilized to investigate emission characteristics.

The dosimetric evaluation encompasses exposure of the films to both X-ray and gamma radiation, followed by thermoluminescent (TL) readout using a standard TLD reader. The assessment includes analysis of dose–response behavior within a defined dose range, measurement reproducibility, investigation of thermal and optical fading, determination of the minimum detectable dose (MDD), and kinetic trap analysis through glow curve deconvolution techniques. The optimized multilayer samples identified based on the most effective configuration of TiO₂ top and bottom layer thicknesses and the intermediate Cu layer are further compared with the commercially available TLD-100 dosimeter. This comparison specifically focuses on thermoluminescent sensitivity and dose–response characteristics. Other performance aspects, such as long-term stability, energy dependence, or performance under clinical and environmental radiation conditions, are beyond the scope of this work. The overall aim is to assess the potential of TiO₂/Cu/TiO₂ multilayer thin films as a promising alternative dosimetric material relative to conventional TLD-100.

1.7 Thesis outline

This thesis is organized into five chapters to systematically present the research process and findings. Chapter 1 introduces the study by outlining the background, problem statement, research motivation, objectives, scope, research gap, and the structure of the thesis, providing a comprehensive framework for the investigation.

Chapter 2 presents a review of the fundamental principles of thermoluminescence, key dosimetric materials, and previous studies related to TiO₂ thin films in radiation dosimetry. It also covers relevant theoretical models and summarizes significant experimental findings from the literature. Chapter 3 describes the experimental methodology, including materials selection, deposition of multilayer thin films using radio frequency (RF) and direct current (DC) sputtering techniques, and the characterization methods employed. These include X-ray diffraction (XRD), field emission scanning electron microscopy (FE-SEM), atomic force microscopy (AFM), ultraviolet-visible (UV–Vis) spectroscopy, photoluminescence (PL) spectroscopy, and thermoluminescence dosimetry (TLD) protocols.

Chapter 4 presents and analyzes the results obtained from structural, morphological, optical, and dosimetric evaluations, with emphasis on glow curve analysis and kinetic modeling. Finally, Chapter 5 summarizes the major findings of the study, assesses the extent to which the research objectives were fulfilled, discusses limitations encountered during the investigation, and proposes recommendations for future research.

CHAPTER 2

LITERATURE REVIEW

2.1 Introduction

This chapter reviews the theoretical and experimental background relevant to this research. It begins with the principles of thermoluminescence (TL), including energy storage and release, radiation sources, and interactions of ionizing radiation with matter, followed by the characteristics and applications of conventional TLDs in medical and industrial dose assessment. Thin-film dosimetry is introduced as an alternative to bulk materials, offering advantages such as higher spatial resolution and surface conformity.

The focus then shifts to titanium dioxide (TiO_2) as a promising dosimetric material due to its optical and luminescent properties. Prior work on thin-film TL systems, including doped and multilayer structures, is reviewed to show how fabrication methods and structural design influence performance. Particular attention is given to $\text{TiO}_2/\text{Cu}/\text{TiO}_2$ multilayers, where the Cu interlayer modifies trap distributions and charge recombination, providing a structural route beyond chemical doping. This context establishes the rationale for exploring multilayer $\text{TiO}_2/\text{Cu}/\text{TiO}_2$ thin films in the present study.

2.2 Luminescence phenomena

Luminescence refers to the light emission resulting from electronic excitation in materials, with specific excitation mechanisms offering direct relevance to thin-film dosimetry. Photoluminescence, for instance, is widely used to probe defect states in TiO_2 , where peaks near 400–500 nm are associated with oxygen vacancies (Zhou et

al., 2019). In contrast, radioluminescence helps assess radiation response in multilayer oxides through emission intensity correlated with trap density (Rahman et al., 2020). The distinction between fluorescence ($\tau \leq 10^{-8}$ s) and phosphorescence ($\tau \geq 10^{-8}$ s) is crucial, as TiO₂ systems often exhibit both fast band-edge emission and slower defect-mediated afterglow, which is exploited in TLDs (Chen & McKeever, 1997; Lakshminarayana et al., 2017).

Thermoluminescence provides a time-integrated record of radiation dose, as demonstrated in oxide nanomaterials and multilayer thin films (Wang et al., 2018). These luminescence processes form the theoretical basis for understanding defect-related emission and glow curve behavior in TiO₂/Cu/TiO₂ multilayer dosimetric systems. Table. 2.1 presents a list of luminescence phenomena and the techniques utilized to stimulate them.

Table 2.1 The phenomenon of luminescence and the methods of stimulation (Valeur & Berberan-Santos, 2012).

Luminescence phenomenon	Method of excitation
Bioluminescence	Biochemical reactions
Cathodoluminescence	Electron beam
Chemiluminescence	Chemical reactions
Electroluminescence	Electric field
Photoluminescence	UV and infrared light
Piezoluminescence	Pressure (10 tons m ⁻²)
Triboluminescence	Friction
Radioluminescence	Ionizing radiation
Sonoluminescence	Sound waves
Fluorescence Phosphorescence Lyoluminescence Thermoluminescence	Ionizing radiation, UV, and visible light

2.2.1 The luminescence centers in the (TL) light emission

Luminescent centers are structural defects or dopant atoms embedded in the host lattice that act as discrete sites for capturing and releasing charge carriers. Instead of considering them only in general terms, research in oxide-based thin films shows

that such centers strongly influence the shape and intensity of TL glow curves. For example, oxygen vacancies in TiO_2 create deep-level traps within the band gap, which contribute to characteristic TL peaks under ionizing radiation (Bharti et al., 2016). Similar findings were reported by Morozova et al. (2001), who observed that dopants such as Cu^{2+} enhance carrier trapping efficiency, thereby increasing light yield. These studies confirm the theoretical role of luminescent centers as recombination sites (Furetta, 2003b), but they also demonstrate their practical importance in tailoring TL sensitivity in thin film dosimetric systems.

2.2.2 TL: Historical perspective and research Use

The phenomenon of TL has been recognized since Boyle's early observations of glowing diamonds, but its scientific relevance to dosimetry became apparent in the mid-20th century, when the need for reliable radiation monitoring grew. McKeever (1985) defined TL as the thermally stimulated emission of light following prior radiation absorption, a description still foundational today. Since the 1940s, TL has been systematically applied in dosimetry, and extensive studies have demonstrated its reliability for recording accumulated radiation doses (Duragkar et al., 2019). Beyond radiation protection, TL has also been utilized as a chronological tool in archaeology and geology (Chen & McKeever, 1997). In recent decades, the focus has shifted toward nanostructured and thin-film TL materials, where reduced dimensionality allows for enhanced trapping and controlled luminescence properties (Rathore et al., 2023). This evolution illustrates how the historical foundation of TL has developed into a modern research tool for advanced applications.

2.2.3 TL dosimetry materials

The effectiveness of TL materials depends on their ability to store energy in metastable traps and release it as light during heating. Classical studies established that insulating or semiconducting hosts such as LiF, CaF₂, and Al₂O₃ could be tailored through dopants to enhance trap depth and stability (Bos, 2006). Daniels et al. pioneered TL as a dosimetric technique, and subsequent development of LiF: Mg, Ti (TLD-100) by Harshaw Chemical Company set the standard for commercial TL detectors (Bhatt & Kulkarni, 2014). Current research has expanded to a wide variety of hosts, such as Li₂B₄O₇: Mn, Al₂O₃:C, and BeO, each optimized for specific applications (Bos, 2017). More recently, investigations have extended into nanostructured and thin-film oxide systems, where defect engineering enables enhanced sensitivity at reduced material quantities (Ding et al., 2020).

Understanding TL mechanisms in these materials requires advanced experimental techniques such as glow curve deconvolution, photoluminescence, and electron paramagnetic resonance to map trap distributions and recombination dynamics. Such studies not only explain the dosimetric performance of conventional phosphors but also provide insight into novel multilayer thin films, including TiO₂/Cu/TiO₂ systems, where engineered interfaces play a critical role in trap-assisted luminescence (Bhatt and Kulkarni, 2014). Table 2.2 presents some characteristic dosimetric properties of the frequently utilized TL materials for radiation dosimetry.

Table 2.2 Lists of general characteristics of commercial TL materials dosimeters (Bhatt and Kulkarni, 2014).

TLD type	Z_{eff}	Main peak (°C)	Relative Sensitivity	Fading (dark room)	Useful dose range
LiF: Mg,Ti	8.14	200	1	5% per year	$20\mu - 10\text{Gy}$
LiF: Mg, Cu, P	8.14	210	40	5% per year	$0.2\mu - 10\text{Gy}$
$\text{Li}_2\text{B}_4\text{O}_7$: Mn	7.30	220	0.40	4% per month	$0.1\text{mG} - 3\text{Gy}$
$\text{Li}_2\text{B}_4\text{O}_7$: Cu	7.30	205	8	10% per 2 months	$10\mu - 10^3\text{Gy}$
MgB_4O_7 : Dy or Tm	8.40	190	6 – 7	4% per month	$5\mu\text{Gy} - 50\text{Gy}$
BeO	7.10	190	~ 1.00	8% per 2 months	$0.1 - 0.5\text{Gy}$
CaSO_4 : Dy	15.30	220	30	1% per 2 months	$2\mu\text{Gy} - 10\text{Gy}$
CaF_2 : Dy	16.30	215	15	8% per 2 months	$10\mu - 10\text{Gy}$
Al_2O_3 : C	10.20	190	60	5% per year	$0.1\mu - 10\text{Gy}$

2.2.4 Mechanism of TL

The mechanism of thermoluminescence is widely understood within the framework of solid-state physics, but its detailed investigation provides important insights into the dosimetric performance of different materials. TL arises from the trapping of charge carriers in metastable defect levels within the band gap of insulators and semiconductors, followed by their release during thermal stimulation. Recent studies have shown that the distribution, depth, and stability of these traps largely dictate the glow curve structure and sensitivity of TL materials (Chen & McKeever). In thin-film dosimetric systems, particularly TiO_2 -based multilayers, trap populations can be significantly altered by structural defects, dopant incorporation, and interfacial effects, making the mechanism central to understanding their radiation response (Wang et al., 2020). As illustrated in Figure 2.1, both the electron and h^+ traps are unoccupied before irradiation, allowing for a state of equilibrium between electrons and holes (Rivera, 2012).

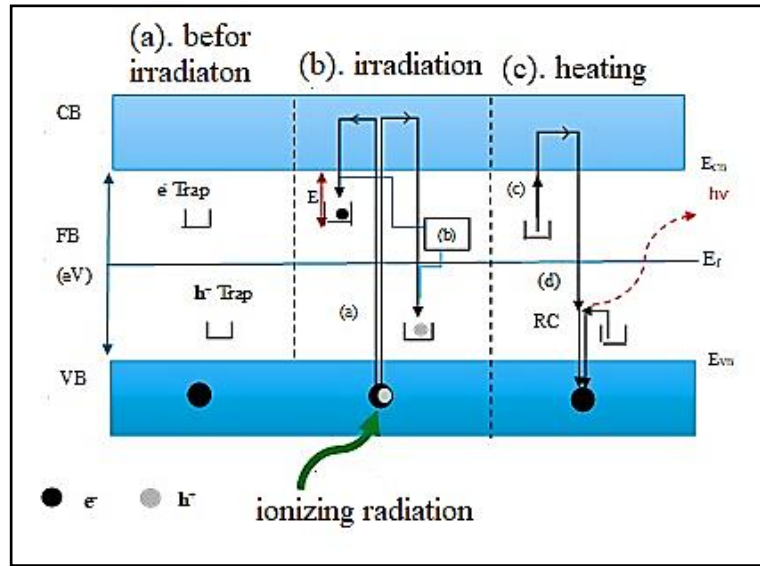


Figure 2.1 The thermoluminescence phenomenon process, where transitions **a**, **b**, **c**, and **d** represent the different electron transitions (McKeever, 1995a).

2.2.4(a) Before irradiation

Before irradiation, electrons predominantly occupy the valence band, leaving defect-related traps in the band gap unfilled. These traps, which may arise from oxygen vacancies, substitutional dopants, or lattice distortions, act as potential capture sites for charge carriers (Rivera, 2012). In TiO_2 , for instance, oxygen vacancies introduce electron traps just below the conduction band, while cation-related defects can produce hole traps near the valence band (Gurylev, 2021). The presence and concentration of these traps strongly influence subsequent TL processes, as they determine the number of carriers that can be stored upon irradiation.

2.2.4(b) Irradiation

When a thermoluminescent material is exposed to ionizing radiation with energy above its band gap, electrons are promoted from the valence band to the conduction band, leaving behind holes in the valence band. These free carriers are subsequently captured by defect-related traps within the band gap. The efficiency of

this process depends strongly on the type and distribution of traps present. In oxide-based materials, oxygen vacancies often act as electron traps near the conduction band, while cation defects can function as hole traps near the valence band (Rivera, 2012; Gurylev, 2021). Experimental studies have confirmed that radiation exposure increases the population of trapped carriers, which directly correlates with the intensity of thermoluminescence upon heating (Bos, 2006). In $\text{TiO}_2/\text{Cu}/\text{TiO}_2$ multilayer systems, the irradiation stage is particularly important because the presence of interfacial states and Cu-related defects enhances trapping efficiency, thereby modifying the dose–response behavior.

2.2.4(c) Heating

Upon heating, trapped carriers acquire sufficient thermal energy to escape from their metastable states into the conduction or valence bands. These free carriers migrate until they recombine at luminescent centers, releasing energy in the form of photons (McKeever, 1995a). The spectral distribution of this emission depends on the depth of the trap and the nature of the recombination center, with shallow traps producing low-temperature glow peaks and deep traps producing high-temperature peaks. Several studies have demonstrated that glow curve deconvolution provides insight into trap depth and kinetics, thereby linking the observed TL signal to the underlying defect structure (Chen & McKeever, 1997; Furetta, 2003b).

In TiO_2 thin films, defect-mediated recombination often results in broad visible emissions attributed to oxygen vacancies, while Cu incorporation introduces additional recombination pathways that enhance photon yield. These findings highlight how the heating stage not only produces detectable luminescence but also

reveals the defect landscape of the material, making it a powerful diagnostic tool for thin-film dosimetry research.

Due to the process of photon emission, which includes releasing a few traps at various energies, the charge carriers are released at different temperatures, yielding a glow curve that is characteristic of a material exhibiting one or more peaks. This mechanism is critical to elucidating radiation dosimetry as it shows that the number of released photons is proportional to the dose of absorbed radiation. However, some electrons and holes are trapped in semiconductors or insulators: electrons in e^- trap and holes in h^+ trap or recombination centers (RC). The heating of the material can cause electrons and holes to escape from these traps via thermal stimulation (TS). The Arrhenius Equation. 2.1 explains the probability (p) of an electron being released from a trap per unit of time.

$$p = \text{sexp} \left(-\frac{E}{kT} \right) \quad (2.1)$$

The pre-exponential factor S (s^{-1}) is referred to as the frequency factor or the attempt-to-escape factor (not temperature dependent), which is dependent on the rate at which an electron is incident on the trap. (E) denotes the trap depth or activation energy needed to release an electron into the CB. It is measured, in (eV), from the trap level to the bottom of the CB. In the case of a hole trap, (E) is measured from the trap to the top of the VB. (E) and (S) are key as trap parameters. (T) and (k) represent absolute temperature and Boltzmann's constant (i.e., 8.617×10^{-5} eV/K), respectively (Furetta, 2003a).

S and E are important because they control the expulsion of an electron from the trap at a specific temperature. Equation. 2.2 expresses the lifetime (τ) of the charge carrier

in the metastable condition (i.e., where the charge carriers are trapped) at temperature T:

$$\tau = p^{-1} \quad (2.2)$$

In addition, if T_0 is the temperature at which the material is subjected to radiation, subsequently any electrons and holes will stay trapped at the e^- trap and h^+ trap or RC, respectively, for a protracted duration, even after exposure to radiation in the case of $E \gg T_0$ (K). The possibility of partition increases when the temperature of the material increases from T_0 (K) to T (K). Afterward, the trapped electrons are liberated from the e^- -trap and drift about in the conduction band pending recombination of the electrons in the h^+ trap, or RC. Thus, RC attains the maximum state of excitation and then rebounds to the ground state by the process of light emission ($h\nu$) or thermoluminescence (TL). Recombination causes light emission, also referred to as "radiative" transitions, for luminescence.

In contrast, during a non-radiative transition, no light is emitted, and the released energy is observed only as phonon emission (lattice vibrations). In TL, at a given heating time t , the TL intensity $I(t)$ (in photons per second) depends on the recombination rate of electrons (e^-) and holes (h^+) at recombination centers (RC). If m (m^{-3}) represents the concentration of trapped charge carriers at RC, the TL intensity can be expressed as an equation. 2.3:

$$I(t) = -\frac{dm}{dt} = -\frac{dn}{dt} = np = n_s \exp\left(-\frac{E}{kT}\right) \quad (2.3)$$

The negative sign indicates the decrease in the concentration of trapped carriers (e^- or h^+) as recombination proceeds. Equation. 2.3 therefore describes the release and transfer of charges within the crystal lattice, which gives rise to TL emission.

2.3 Radiation sources in TL dosimetry studies

(TLDs) are typically evaluated under controlled radiation fields, and the choice of source strongly influences the observed glow curve characteristics, sensitivity, and dose–response behavior. Different studies have employed gamma, beta, and X-ray sources to investigate material performance, each providing insight into specific aspects of trapping and recombination processes. Gamma-emitting isotopes such as ^{60}Co and ^{137}Cs are widely used in TL studies due to their well-characterized photon energies and dose rates. For example, Bos (2006) and Bhatt & Kulkarni (2014) reported consistent linear dose–response of conventional phosphors such as LiF:Mg,Ti , and $\text{Al}_2\text{O}_3\text{:C}$ under gamma irradiation, establishing these sources as reference standards in dosimetry research. Gamma rays also allow examination of bulk sensitivity in thin films, where interaction probabilities differ from conventional powders.

Beta-emitting sources, particularly ^{90}Sr – ^{90}Y , are employed to probe shallow dose distributions and surface sensitivity. Villarreal-Barajas et al., (2002) demonstrated that nanostructured oxide thin films exhibit strong thickness-dependent TL yield under beta irradiation, highlighting the role of defect density and trapping depth in films below 200 nm. Such findings are relevant for TiO_2 multilayers, where the top layer thickness influences both absorption and charge carrier transport.

X-ray sources have gained attention in recent years due to their direct relevance to diagnostic and therapeutic radiology. Luo et al. (2017) showed that oxide nanostructures display enhanced TL sensitivity to diagnostic X-rays, attributed to the presence of shallow traps and surface states. In our earlier work (Idriss et al., 2023), we presented a preliminary study on the effect of TiO_2 layer thickness on radiation

response. More recently, we demonstrated that X-ray irradiation of TiO₂ multilayer thin films with a Cu interlayer significantly modifies the glow-curve characteristics due to the formation of interfacial traps and altered recombination kinetics. Building on these findings, the present thesis expands the investigation to TiO₂/Cu/TiO₂ multilayer systems, reinforcing the suitability of X-ray excitation for probing defect states in oxide thin-film dosimeters.

Overall, the literature demonstrates that radiation sources are not only chosen for practical convenience but also to probe specific material responses. Gamma irradiation is often used for calibration and bulk sensitivity studies, beta irradiation for surface and thin-film effects, and X-rays for investigating trap-assisted recombination in oxide films. For the present work, X-ray sources are most relevant because they provide a direct means to study the influence of multilayer architecture on TL response, particularly the role of Cu interlayers and TiO₂ thickness variation.

2.3.1 Interaction of radiation with matter in TL dosimetry

Radiation interacts with matter through several well-established mechanisms, primarily photoelectric absorption, Compton scattering, and pair production, each dominant in different photon energy ranges (Knoll, 2010). While these interactions are fundamental to radiation physics, their practical relevance to thermoluminescent dosimeters varies, and only some directly contribute to the generation of trapped charge carriers responsible for TL. As shown in Figure 2.2, photo-absorption, pair production, and Compton scattering dominate the total cross section at low photon energies, high energies, and intermediate energy ranges, respectively.

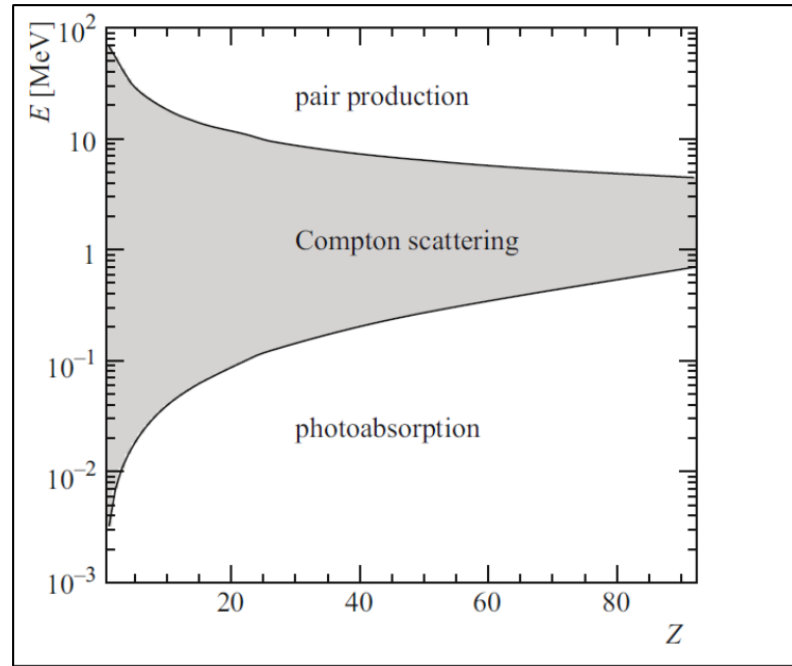


Figure 2.2 The bottom curve shows the trend of the photon energy E as a function of the target substance's atomic number Z , below which photoelectric absorption (photoabsorption) is the main response mechanism, while the upper curve shows the energy above which pair production is dominant. The shaded area between the two curves represents the Compton scattering-dominated field (Fabjan, 2020).

2.3.2 Photoelectric effect

The photoelectric effect is the most important mechanism for TL materials, particularly in low- to medium-energy photons typical of diagnostic X-rays. When a photon is absorbed by a material, it ejects an electron, creating an electron–hole pair that can be captured in defect-related traps (Bos, 2006; Khan & Gibbons, 2014). Materials with higher effective atomic numbers exhibit stronger photoelectric absorption, enhancing TL sensitivity. In TiO_2 thin films, studies have shown that oxygen vacancies and other defect centers act as effective electron traps, and variations in film thickness modify absorption probabilities and glow curve characteristics. These findings demonstrate that optimizing the density and type of defects can directly improve dosimetric performance. Figure 2.3 provides a schematic depiction of the photoelectric effect (Khan and Gibbons, 2014).

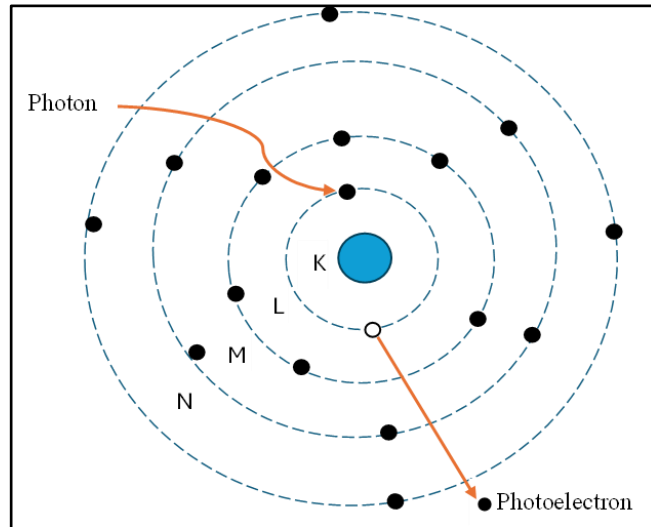


Figure 2.3 Schematic diagram for photoelectric interaction (Khan and Gibbons, 2014).

2.3.3 Compton scattering

Compton scattering dominates at intermediate photon energies, where photons transfer part of their energy to loosely bound electrons, resulting in scattered photons and recoil electrons (Ziessman et al., 2006). While Compton interactions contribute to overall energy deposition, their effect on TL efficiency is relatively indirect, as the scattered electrons are less likely to be captured in the metastable traps responsible for luminescence. Experimental studies in thin-film oxides suggest that Compton events primarily influence bulk energy deposition rather than specific trap population dynamics. Figure. 2.4 illustrates Compton scattering, showing the interaction between the incident photon and electrons.

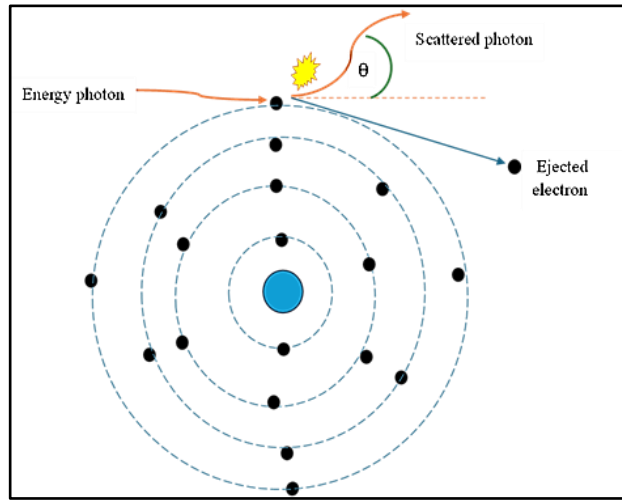


Figure 2.4 The schematic diagram for Compton interaction (Khan and Gibbons, 2014).

2.3.4 Pair production

Pair production (Figure 2.5) becomes significant only at photon energies above 1.02 MeV, where photons interact with the nuclear field to produce electron–positron pairs (Tuchin, 2010; Khan & Gibbons, 2014). For most practical TL applications, diagnostic X-rays, therapeutic gamma rays, or beta sources, pair production is negligible. Consequently, its contribution to trap formation in $\text{TiO}_2/\text{Cu}/\text{TiO}_2$ multilayers is minimal.

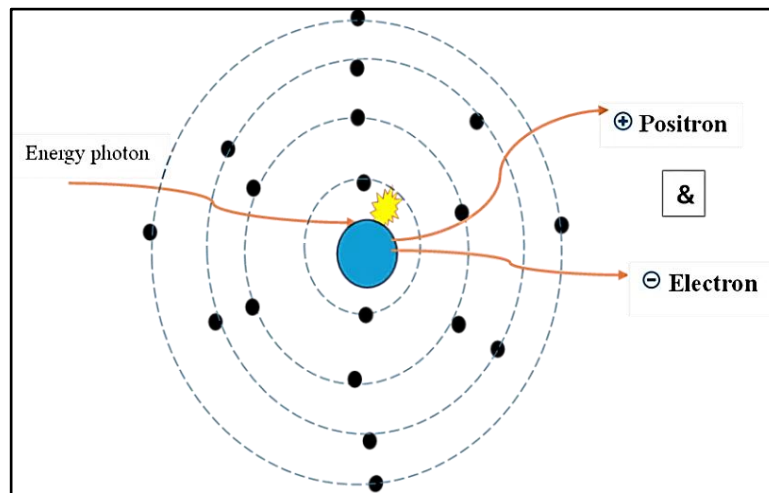


Figure 2.5 Pair the production interaction schematic exhibiting annihilation radiation (Khan and Gibbons, 2014).

2.3.5 Relevance to TL materials and thin films

Taken together, the literature indicates that the photoelectric effect is the primary interaction mechanism underlying TL dosimetry, directly linking photon absorption to charge trapping and luminescence emission. Understanding how photoelectric absorption interacts with material defects allows researchers to optimize multilayer $\text{TiO}_2/\text{Cu}/\text{TiO}_2$ films for enhanced TL response. Manipulating layer thickness, defect density, and dopant concentration can tune absorption efficiency and trap occupancy, providing tailored dosimetric performance under specific radiation sources (Rahman et al., 2020). Compton scattering and pair production, while relevant for general energy deposition, have a secondary or negligible role in the direct operation of TL detectors

2.4 Applications of thermoluminescent dosimeters (TLDs)

Thermoluminescent dosimeters are widely used in personal, clinical, environmental, and radiotherapy dosimetry due to their high sensitivity, tissue equivalence, and reproducibility. Early work by Daniels et al. (1953) established the feasibility of TL for radiation measurement, and subsequent studies have expanded its application in medical physics, environmental monitoring, and occupational safety (Azorín Nieto, 2004).

2.4.1 Diagnostic radiology

TLDs have been employed to quantify patient doses from diagnostic X-rays, particularly using $\text{LiF}:\text{Mg}$, Ti , and tissue-equivalent $\text{Li}_2\text{B}_4\text{O}_7:\text{Mn}$ phosphors (Rivera-Montalvo, 2016). These studies show that TLDs can accurately map dose distribution

in phantoms and patients, providing critical data for optimizing imaging protocols and reducing unnecessary exposure.

2.4.2 Radiotherapy

In radiotherapy, TLDs are used for in vivo and phantom dosimetry, including verification of machine output, beam uniformity, and dose distributions for both internal and external treatments (Azorin et al., 1990). Recent research demonstrates that micro- and nanoscale TL materials can enhance spatial resolution and sensitivity in high-gradient fields, which is particularly relevant for modern intensity-modulated radiotherapy.

2.4.3 Radiation protection and personnel dosimetry

Several studies have validated TLD use for occupational dose monitoring in medical, industrial, and nuclear environments (Murthy & Reddy, 2008). Comparative studies indicate that thin-film and microdosimeter configurations provide rapid, reliable readings while maintaining tissue equivalence (Christensen et al., 1982).

2.4.4 Environmental monitoring

TLDs have been applied in environmental dose assessment using passive detectors such as LiF:Mg,Ti, CaF₂: Mn, and Al₂O₃:C (Ranogajec-Komor, 2002; Mobit & Kron, 2006). Research emphasizes the importance of material sensitivity and detector calibration for detecting low-level radiation in natural and anthropogenic environments.